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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10084204	FILING DATE 02/28/2002	CLASS 430	SUBCLASS	GAU 1752	EXAMINER
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**APPLICANTS: Suzuki Takako; Tamura Sachiko; Doi Kousuke; Kohara Hidekatsu;
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**CONTINUING DATA VERIFIED:
THIS APPLICATION IS A DIV OF 09/322,978 06/01/1999

** FOREIGN APPLICATIONS VERIFIED:
JAPAN 10-155213 06/04/1998

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiner's initials	<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO Q67844
TITLE : Positive photoresist composition and process for forming resist pattern using same U.S.DEP'T. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)		

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drwg. Figs.Drwg. Print Fig.		
TERMINAL DISCLAIMER		Primary Examiner	Application Examiner	
PREPARED FOR ISSUE				
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